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The growth and characterization of Si and Ge nanowires grown from reactive metal catalysts

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Due to communication errors the article was not published within the special issue for which it was written. For completeness of the scientific record, we are now withdrawing the originally published version, on behalf of the Guest Editor, Journal Editors and Taylor & Francis. We apologise to our readers for this.

The version of record of the article will now be published in the “Electron Microscopy and Diffraction of Defects, Nanostructures, Interfaces and Amorphous Materials: Conference to Mark the Retirement of Professor David Cockayne FRS” special issue of *Philosophical Magazine* published [here](#). The latest version will be the definitive and citable version of the article.

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